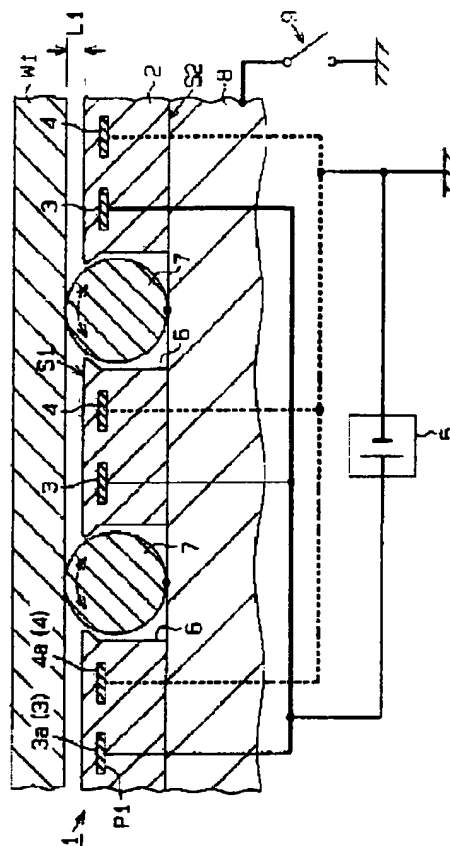


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 APPLICANT : IBIDEN CO LTD;
 INVENTOR : ADACHI SHINJI;
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 TITLE : ELECTROSTATIC CHUCK



ABSTRACT : PROBLEM TO BE SOLVED: To provide an electrostatic chuck which gives little damage to a work to be attracted and moreover assures extremely low particle generation coefficient.

SOLUTION: In this electrostatic chuck 1, an objective work W1 is attracted electrostatically to the chuck surface S1 when the electrical power is supplied to the chuck electrode layers 3 and 4 formed on the insulated base material 2. A plurality of recesses 6 opening at the chuck surface S1 are provided to the insulated base material 2. Within the recess 6, almost spherical work supporting body 7 is fitted with play. In this case, a part of the work supporting body 7 is projected from the chuck surface S1.

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